

CLAIMS

What is claimed is:

1. A method for coating an uniform resist layer onto a plurality of non-planar sliders,
said method comprising:

spinning an elastic layer on a wafer;

curing said elastic layer;

spinning a resist layer on said elastic layer;

peeling said resist layer and said elastic layer together off from said wafer;

applying said peeled resist layer and elastic layer onto a plurality of
magnetic heads with said resist layer in direct contact with said plurality of
magnetic heads; and

peeling said elastic layer off from said resist layer such that said resist layer
remains attaching to said plurality of magnetic heads.

1 2. The method of Claim 1, wherein said elastic layer is poly-dimethyl siloxane.

1 3. The method of Claim 1, wherein said resist layer is a positive tone resist layer.

1 4. The method of Claim 1, wherein said wafer is a silicon wafer.

1 5. The method of Claim 1, wherein said curing further includes curing said elastic
2 layer at approximately 110 °C for about 8 minutes.

1 6. The method of Claim 1, wherein said applying further includes applying with a
2 roller.

1 7. The method of Claim 6, wherein said applying further includes applying with a
2 roller at approximately 25 °C and pressure at approximately 1 psi.

1 8. The method of Claim 1, wherein said method further includes baking said resist
2 layer at a temperature between approximately 70 °C to 80 °C after said resist layer has
3 been spun on said elastic layer.

1 9. A method for coating an uniform resist layer onto a plurality of non-planar sliders,
2 said method comprising:

3 molding an elastic layer;

4 curing said elastic layer;

5 spinning a resist layer on said elastic layer;

6 applying said peeled resist layer and elastic layer onto a plurality of
7 magnetic heads with said resist layer in direct contact with said plurality of
8 magnetic heads; and

9 peeling said elastic layer off from said resist layer such that said resist layer
10 remains attaching to said plurality of magnetic heads.

- 1 10. The method of Claim 9, wherein said elastic layer is poly-dimethyl siloxane.
- 1 11. The method of Claim 9, wherein said resist layer is a positive tone resist layer.
- 1 15. The method of Claim 9, wherein said curing further includes curing said elastic
2 layer at approximately 110 °C for about 8 minutes.
- 1 16. The method of Claim 9, wherein said applying further includes applying with a
2 roller.
- 1 17. The method of Claim 16, wherein said applying further includes applying with a
2 roller at approximately 25 °C and pressure at approximately 1 psi.
- 1 18. The method of Claim 9, wherein said method further includes baking said resist
2 layer at a temperature between approximately 70 °C to 80 °C after said resist layer has
3 been spun on said elastic layer.